AMENDMENTS TO THE CLAIMS

1. (Currently Amended) A lithographic material that contains a polymer bearing at least one polyhedral oligomeric silsesquioxane group, wherein the alkyl substituents of the polyhedral oligomeric silsesquioxane group[[-that]] are not linked to the main chain (backbone) of the polymer[[-]] and contain[[ing]] up to 3 carbon atoms.

2. (Currently Amended) A positive tone lithographic material that contains a polymer bearing at least one polyhedral oligomeric silsesquioxane group, wherein the alkyl substituents of the polyhedral oligomeric silsesquioxane group[[-that]] are not linked to the main chain (backbone) of the polymer[[-]] and contain[[ing]] up to 3 carbon atoms.

3. (Currently Amended) A chemically amplified positive tone lithographic material that contains a polymer bearing at least one polyhedral oligomeric silsesquioxane group, wherein the alkyl substituents of the polyhedral oligomeric silsesquioxane group[[-that]] are not linked to the main chain (backbone) of the polymer[[-]] and contain[[ing]] up to 3 carbon atoms.

4. (Currently Amended) A chemically amplified positive tone lithographic material that contains a polymer bearing at least one polyhedral oligomeric silsesquioxane group, wherein the alkyl substituents of the polyhedral oligomeric silsesquioxane group[[-that]] are not linked to the main chain (backbone) of the polymer[[-]] and comprise [[being]] ethyl groups.

5. (Currently Amended) A chemically amplified positive tone lithographic material that contains a (meth) acrylic polymer, bearing at least one polyhedral oligomeric silsesquioxane group, wherein the alkyl substituents of the polyhedral oligomeric silsesquioxane group[[-that]] are not linked to the main chain (backbone) of the polymer[[-]] and comprise [[being]] ethyl groups.

6. (Currently Amended) A lithographic process comprising exposing ~~including a 157 nm exposure of~~ a lithographic material containing a polymer[[,]] bearing at least one polyhedral oligomeric silsesquioxane group to 157 nm radiation.

7. (Currently Amended) A lithographic process comprising exposing ~~including a 157 nm exposure, or generally VUV, or EUV exposure, of~~ a lithographic material containing a polymer[[,]] bearing at least one polyhedral oligomeric silsesquioxane group to 157 nm radiation, or VUV exposure, or EUV exposure, wherein the alkyl substituents of the polyhedral oligomeric silsesquioxane group[[-that]] are not linked to the main chain (backbone) of the polymer[[-]] and contain[[ing]] up to 3 carbon atoms.

8. (Currently Amended) A lithographic process comprising exposing ~~including a 157 nm exposure, or generally VUV, or EUV exposure, of~~ a lithographic material containing a polymer[[,]] bearing at least one polyhedral oligomeric silsesquioxane group to 157 nm radiation, or VUV exposure, or EUV exposure, wherein the alkyl substituents of the polyhedral oligomeric silsesquioxane group[[-that]] are not linked to the main chain (backbone) of the polymer and comprise [[- being]] ethyl groups.

9. (Currently Amended) A bilayer lithographic process comprising exposing [[with]] a positive tone lithographic material containing a polymer[[,]] bearing at least one polyhedral oligomeric silsesquioxane group to radiation, wherein the alkyl substituents[[-that]] of the polyhedral oligomeric silsesquioxane group are not linked to the main chain (backbone) of the polymer[[-]]and contain[[ing]] up to 3 carbon atoms.

10. (Currently Amended) A bilayer lithographic process comprising exposing [[with]] a positive tone lithographic material containing a polymer[[,]] bearing at least one polyhedral oligomeric silsesquioxane group to radiation, wherein the alkyl substituents[[-that]] of the polyhedral oligomeric silsesquioxane group are not linked to the main chain (backbone) of the polymer and comprise [[- being]] ethyl groups.